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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/811,360	03/26/2004	James D. Beasom	125.008US02	2091
75	90 08/25/2004	EXAMINER		INER
Fogg, Slifer & Polglaze, P.A. P.O. Box 581009			LUU, CHUONG A	
Minneapolis, MN 55458-1009			ART UNIT	PAPER NUMBER
			2825	

DATE MAILED: 08/25/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
Office Action Commons	10/811,360	BEASOM, JAMES D.				
Office Action Summary	Examiner	Art Unit				
	Chuong A Luu	2825				
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address				
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply - If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	86(a). In no event, however, may a reply be time within the statutory minimum of thirty (30) days will apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on						
2a) This action is FINAL . 2b) ⊠ This	This action is FINAL . 2b)⊠ This action is non-final.					
3) Since this application is in condition for allowan	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is					
closed in accordance with the practice under E	x parte Quayle, 1935 C.D. 11, 45	53 O.G. 213.				
Disposition of Claims						
4) Claim(s) <u>1-55</u> is/are pending in the application.)⊠ Claim(s) <u>1-55</u> is/are pending in the application.					
4a) Of the above claim(s) is/are withdraw	4a) Of the above claim(s) is/are withdrawn from consideration.					
5)⊠ Claim(s) <u>11-37</u> is/are allowed.						
6) Claim(s) <u>1-4, 6-10, 38-53 and 55</u> is/are rejected	·					
7) Claim(s) <u>5 and 54</u> is/are objected to.						
8) Claim(s) are subject to restriction and/or	election requirement.					
Application Papers						
9)☐ The specification is objected to by the Examine						
10) The drawing(s) filed on is/are: a) acce	epted or b) \square objected to by the E	Examiner.				
Applicant may not request that any objection to the		` '				
Replacement drawing sheet(s) including the correcti	- · · · · · · · · · · · · · · · · · · ·	• •				
11)☐ The oath or declaration is objected to by the Ex-	aminer. Note the attached Office	Action of form PTO-152.				
Priority under 35 U.S.C. § 119						
 12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priority application from the International Bureau 	s have been received. s have been received in Application ity documents have been received (PCT Rule 17.2(a)).	on No ed in this National Stage				
* See the attached detailed Office action for a list of	of the certified copies not receive	d.				
Attachment(s)	_					
1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948)	4) Interview Summary Paper No(s)/Mail Da					
Paper No(s)/Mail Date <u>3/26/04</u> .		atent Application (PTO-152)				

Application/Control Number: 10/811,360

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DETAILED ACTION

PRIOR ART REJECTIONS

Statutory Basis

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

The Rejections

Claims 1-4, 6-9, 38-41, 44-53 and 55 are rejected under 35 U.S.C. 103(a) as being unpatentable over Hshieh (U.S. 6,172,398 B1) in view of Muller et al. (Device Electronics For Integrated Circuits).

Hshieh discloses the following:

A body region 130 in a substrate 105;

A source 140 in the body region 130;

Hshieh additionally discloses that the substrate and body layer are N+ and p type, respectively (see column 2, lines 49-66; column 3, lines 56-66; column 4, lines 8-34. Figures 3A, 5A-5F).

The only feature not clearly taught in Hshieh is the narrow band gap material which has a band gap narrower than a band gap of the substrate material. However, the reference does state that the substrate and the body are formed in a conventional ion implantation manner. The examiner takes Official Notice that such a band gap is well

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known in the art. In support of this assertion the examiner has cited Device Electronics

For Integrated Circuits by Muller et al. This textbook discloses the band gap varies due
to the impurities ions implantation formation. Consequently as this is a conventional
method of formation of MOS well known to one of ordinary skill in the art at the time of
applicant's invention, it would have been obvious to one of ordinary skill in the art to
clarify the manner of formation of the MOS with a narrow band gap material which has a
band gap narrower than a band gap of the substrate material of Hshieh by using the
teaching of Muller.

For Muller see pages 54-56.

Claims 7, 9-10 and 42-43 are rejected under 35 U.S.C. 103(a) as being unpatentable over Hshieh (U.S. 6,172,398 B1) and Muller et al. (Device Electronics For Integrated Circuits) and further in view of Agnello et al. (U.S. 6,406,962 B1).

Hshieh and Muller teach everything above except for disclosing specifically material of the narrow band gap material; tilt angle implantation; germanium ions dopant. Further, Agnello as showing that in order to create an adequate contact to the source by tilt angle implantation with germanium ion that would convert the silicon substrate to GeSi material. Therefore, it would have been obvious to one of ordinary skill in the art to read the teaching of Agnello and make the device formed by the combination of Hshieh and Muller have the semiconductor structure to exceed its performance criteria.

For Agnello see column 3, lines 42-50; column 13, lines 1-15.

Allowable Subject Matter

Claims 5 and 54 are objected to as being dependent upon a rejected base claim,

but would be allowable if rewritten in independent form including all of the limitations of

the base claim and any intervening claims.

Claims 11-37 are allowed.

Conclusion

Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Chuong A Luu whose telephone number is (571) 272-

1902. The examiner can normally be reached on M-F (6:30-3:00).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Matthew Smith can be reached on (571) 272-1907. The fax phone number

for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the

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CAL August 9, 2004